

Microposit MF-319

Product	Microposit MF-319 Developer
Manufacturer	Rohm And Haas Electronic Materials LLC
Composition	95.0–99.0% water , 1.0–5.0% tetramethylammonium hydroxide , <1.0% polyalkylene glycol; liquid
Synonyms	319, MF-319
Typical Uses	Developer for photolithography
Hazards	<p>300</p>  <p>Corrosive to metals CATEGORY 1, Specific target organ toxicity – single exposure CATEGORY 1 (oral), Specific target organ toxicity – repeated exposure CATEGORY 1 (dermal), Skin corrosion/irritation CATEGORY 2, Serious eye damage /eye irritation CATEGORY 2A</p>
Storage	Cabinet 13 (bases cabinet in Wet Aisle 1); underneath litho wet decks
Disposal	Pour into wet deck (Litho Wet Deck 1/2, Wet Deck 1A/1B/2A) and rinse copiously with DI water.
Comments	Standard developer for LOR 5B in lift-off bilayer process . Contains 2.45% TMAH; normality of 0.237 N. Login to tool <i>Litho Wet Deck #1 - TMAH</i> or <i>Litho Wet Deck #2 - TMAH</i> when using. Wear PPE when handling: chemical-resistant gloves, acid apron, face shield.
Status	STOCKED



Check First

Please contact a nanoFAB staff member for uses not listed above.